

GEORGE O. SAILE & ASSOCIATES
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TS01-133



September 10, 2001

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From: Stephen B. Ackerman

Subject: Serial No.: 09/905,408
Filing Date: 07/16/01
Inventor: S. H. Chen
Title: Selective Formation of Metal Gate for Dual Gate Oxide
Application

REQUEST TO CORRECT FILING RECEIPT

Dear Sir:

On the copy of the enclosed Filing Receipt, there are errors in the list of Applicants. The second Applicant's name is misspelled. Mr. Tsai's corrected name and residence reads; Minghsing Tsai, Taipei, Taiwan.

Please make the necessary change to correct the error on the Filing Receipt.

If there are any questions, please contact the undersigned attorney at (845) 452-5863. Thank you for your attention to this matter.

Respectfully Submitted,

Stephen B. Ackerman, Reg. No. 37,761

AUG. 30 2001



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APPLICATION NUMBER	FILING DATE	GRP ART UNIT	FIL FEE REC'D	ATTY. DOCKET NO	DRAWINGS	TOT CLAIMS	IND CLAIMS
09/905,408	07/16/2001	2812	710	TS01-133	5	14	2

GEORGE O. SAILE
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POUGHKEEPSIE, NY 12603



CONFIRMATION NO. 3764

FILING RECEIPT



OC000000006487487

Date Mailed: 08/28/2001

Receipt is acknowledged of this nonprovisional Patent Application. It will be considered in its order and you will be notified as to the results of the examination. Be sure to provide the U.S. APPLICATION NUMBER, FILING DATE, NAME OF APPLICANT, and TITLE OF INVENTION when inquiring about this application. Fees transmitted by check or draft are subject to collection. Please verify the accuracy of the data presented on this receipt. If an error is noted on this Filing Receipt, please write to the Office of Initial Patent Examination's Customer Service Center. Please provide a copy of this Filing Receipt with the changes noted thereon. If you received a "Notice to File Missing Parts" for this application, please submit any corrections to this Filing Receipt with your reply to the Notice. When the USPTO processes the reply to the Notice, the USPTO will generate another Filing Receipt incorporating the requested corrections (if appropriate).

Applicant(s)

Sheng Hsiung Chen, Taichung Connty, TAIWAN;
Mingh-Sing Tsai, Taipei, TAIWAN;

Assignment For Published Patent Application

Taiwan Semiconductor Manufacturing Company;

Domestic Priority data as claimed by applicant

Foreign Applications

If Required, Foreign Filing License Granted 08/28/2001

Projected Publication Date: Request for Non-Publication Acknowledged

Non-Publication Request: Yes

Early Publication Request: No

Title

Selective formation of metal gate for dual gate oxide application

Preliminary Class

438

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